

# **ABSTRACT OF THE DISCLOSURE**

An observation position designation section 8 determines a plurality of control points for a wafer pattern formed on a wafer 4 based on CAD data, and generates observation coordinate data D according to the plurality of determined control points, causes a navigation unit 5 to move in accordance with the observation coordinate data D, and automatically and sequentially positions a pattern observation device body 3 on the plurality of observation points for observation.

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